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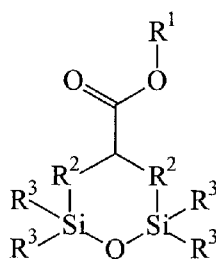
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(54) Title: NOVEL PHOTSENSITIVE BILAYER COMPOSITION



(I)

(57) Abstract: Polymers and co-polymers having monomeric units formed by the polymerization of monomers of the Structure (I), where R¹ is a moiety containing an ethylenically unsaturated polymerizable group, R² is a C₁-C₃ alkylene group, and R³ is a C₁₋₁₀ linear or cyclic alkyl group, a C₆₋₁₀ aromatic or substituted aromatic group, a C₁₋₈ alkoxy methyl, or a C₁₋₈ alkoxy ethyl group, are useful as binder resins for photosensitive compositions, and processes for photolithography in the production of semiconductor devices and materials.

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